

EAST Search History**EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	117	("20020041377" "20020061469" "20020163629" "20030013026" "20030030916" "20030174408" "20040000627" "20040027923" "20040075895" "20040109237" "20040114117" "20040118184" "20040119954" "20040125351" "20040136494" "20040160582" "20040168834" "20040169924" "20040180294" "20040180299" "20040207824" "20040211920" "20040224265" "20040224525" "20040233405" "20040253547" "20040253548" "20040257544" "20040259008" "20040259040" "20040263808" "20040263809" "20050002004" "20050007569" "20050007570" "20050018155" "20050018156" "20050030497" "20050030498" "20050030506" "20050030511" "20050036121" "20050036183" "20050036184" "20050036213"	US-PGPUB; USPAT	OR	ON	2011/03/10 16:57

"20050037269" |
"20050041225" |
"20050042554" |
"20050046813" |
"20050048223" |
"20050052632" |
"20050068639" |
"20050073670" |
"20050074704" |
"20050078286" |
"20050084794" |
"20050088635" |
"20050094114" |
"20050094116" |
"20050094119" |
"20050100745" |
"20050110973" |
"20050117224" |
"20050122497" |
"20050124815" |
"20050134817" |
"20050141098" |
"20050145265" |
"20050145803" |
"20050146694" |
"20050146695" |
"20050147920" |
"20050153424" |
"20050158673" |
"20050161644" |
"20050164502" |
"20050173682" |
"20050174549" |
"20050175940" |
"20050185269" |
"20050190435" |
"20050190455" |
"20050205108" |
"20050213061" |
"20050213072" |
"20050217135" |
"20050217137" |
"20050217703" |
"20050219481" |
"20050219482" |
"20050219499" |
"20050225734" |
"20050225737" |
"20050231694" |
"20050233081" |
"20050237501" |
"20050243292" |
"20050245005" |
"20050253090" |

		"20050259233" "20050259236" "20050264778" "20050270505" "20060098177" "20060177777" "20060256316" "20070159609" "3727620" "5177528" "5274434" "5444529" "5646413" "5684296" "6025206" "6195154" "6281962" "6827816").PN.				
L2	31	(detect\$3 sens\$3) near3 (immersion liquid fluid water) same (load\$3 unload \$3) near2 (wafer substrate workpiece) and (\$5lithograph\$2 exposure).ab.	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L3	7	(detect\$3 sens\$3) near3 (immersion liquid fluid water) with (table support chuck holder) same (load\$3 unload\$3) near2 (wafer substrate workpiece) with (table support chuck holder) and (\$5lithograph\$2 exposure).ab.	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L4	12	(detect\$3 sens\$3) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder) and (\$5lithograph\$2 exposure).ab.	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28

L5	12	(detect\$3 sens\$3) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L6	12	(detect\$3 sens\$3 camera determin\$5) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:28
L7	3	(detect\$3 sens\$3 camera determin\$5) near3 (residual remain \$3 leftover undesir\$4 unwanted stray leak \$3) near (immersion liquid fluid water) with (table support chuck holder) same3 (load\$3 unload\$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:29
L8	5	(detect\$3 sens\$3 camera determin\$5) near3 (residual remain \$3 leftover undesir\$4 unwanted stray leak \$3) near (immersion liquid fluid water) same10 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:29

L9	:3	(detect\$3 sens\$3 camera determin\$5) near3 (residual remain \$3 leftover undesir\$4 unwanted stray leak \$3) near (immersion liquid fluid water) same10 (load\$3 unload \$3) near (wafer substrate workpiece) with (table support chuck holder) and (\$5lithograph\$2 exposure).ab.	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/03/10 17:29
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3/10/2011 5:34:50 PM

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